CLAIMS

I claim:

[c1] 1. An image sensor comprising:

a plurality of pixels formed in a semiconductor substrate, each pixel including a light sensitive element;

a micro-lens over each of said light sensitive elements; and a trench structure surrounding each of said micro-lenses.

- [c2] 2. The image sensor of Claim 1 wherein said trench structure is circular.
- [c3] 3. The image sensor of Claim 1 wherein said trench structure has a rectangular cross-section.
- [c4] 4. The image sensor of Claim 1 wherein the micro-lenses are formed from polymethylmethacrylate (PMMA) or polyglycidylmethacrylate (PGMA).
- [c5] 5. The image sensor of Claim 1 wherein said trench structure has a depth on the order of 0.2 microns.
- [c6] 6. The image sensor of Claim 1 wherein said trench structure is formed in a layer that underlies said micro-lenses.

[c7]	7.	The image sensor of Claim 1 further including a color filter layer between .
	said micro-	lenses and said light sensitive elements.
	o	A picul of an impact according to
[c8]	8.	A pixel of an image sensor comprising:
	a light sensitive element formed in a semiconductor substrate;	
	a micro-lens over said light sensitive element; and	
	a trench structure surrounding said micro-lens.	
[c9]	9.	The pixel of Claim 8 wherein said trench structure is circular.
[c10]	10.	The pixel of Claim 8 wherein said trench structure has a rectangular cross-
	section.	
[c11]	11.	The pixel of Claim 8 wherein the micro-lens is formed from methacrylate (PMMA) or polyglycidylmethacrylate (PGMA).
	polymemyn	montatorylate (1 1411411) or polyglyoldylinelliderylate (1 Givil 1).
[c12]	12.	The pixel of Claim 8 wherein said trench structure has a depth on the order
	of 0.2 micro	ons.
[c13]	13.	The pixel of Claim 8 wherein said trench structure is formed in the material
	that underlies said micro-lenses.	
[c14]	14.	The pixel of Claim 8 further including a color filter layer between said micro-
	lenses and said light sensitive elements.	
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[c15] 15. A method of forming a pixel of an image sensor comprising:

forming a light sensitive element in a semiconductor substrate;

forming a top planarizing layer over said light sensitive element;

forming a trench structure in said top planarizing layer, said trench structure encompassing said light sensitive element; and

forming a microlens within the interior of said trench structure and over said light sensitive element.

- [c16] 16. The method of Claim 15 wherein said trench structure is formed in said top planarizing layer.
- [c17] 17. The method of Claim 15 wherein said trench structure has a rectangular cross section.
- [c18] 18. The method of Claim 15 wherein said trench structure is a closed shape.
- [c19] 19. The method of Claim 15 further including forming a color filter layer between said microlens and said light sensitive element.